

SHEET ____ of ____

INFORMATION DISCLOSURE CITATION PTO-1449	Att'y. Docket No. NMTC-0770	Serial No. 10/02/014
	Applicant MACLEAN, Kevin	Group 2123
	Filing Date 3/15/2002	RECEIVED DEC 10 2002 Technology Center 2100

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
AS	6,014,456	1/11/2000	Tsudaka	382	144	7/15/1996
	6,154,563	11/28/2000	Tsudaka	382	144	12/17/1998
	6,298,473 B1	10/2/2001	Ono, et al.	716	21	12/3/1998
	6,339,836 B1	1/15/2002	Eisenhofer, et al.	716	5	8/24/1998
	6,453,452 B1	9/17/2002	Chang, et al.	716	8	9/16/1998
	6,453,457 B1	9/17/2002	Pierrat, et al.	716	19	9/29/2000
	2002/0100004 A1	7/25/2002	Pierrat, et al.	716	5	3/15/2002
	2002/0152449 A1	10/17/2002	Lin	716	17	4/13/2001
	2002/0152454 A1	10/17/2002	Cote, et al.	716	21	6/7/2002

date past filing
date

EXAMINER:

S. ALH

Date Considered:

12/1/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

NTI Use Only: 770; 243; 1



SHEET ___ of ___

INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.

NMTC-0770

Applicant

MACLEAN, Kevin

Filing Date

3/15/2002

Serial No.

10/098514

RECEIVED

DEC 10 2002

Group Technology Center 2100
2123

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
SD	Cobb, N., et al., "Fast, Low-Complexity Mask Design", SPIE, Vol. 2440, pp. 313-327, February 22-24, 1995.
	Cobb, N., et al., "Experimental Results on Optical Proximity Correction With Variable Threshold Resist Model", SPIE, Vol. 3051, pp. 458-468, March 12-14, 1997.
	Cobb, N., "Fast Optical and Process Proximity Correction Algorithms for Integrated Circuit Manufacturing", Dissertation, University of California at Berkeley, UMI Microform 9902038 (139 pages).
	Toublan, O., et al., "Phase Aware Proximity Correction for Advanced Masks", SPIE, Vol. 4000, pp. 160-170, March 1-3, 2000.
	Anonymous, "Parameterization For Full Shape And Rule Dependent Dissection", IPCOM000009587D, September 4, 2002 (9 pages). <i>late past filing date</i>

EXAMINER:

Date Considered:

12/7/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

NTI Use Only: 770: 243: 1

INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.

NMTC-0770

Applicant

MACLEAN, Kevin

Filing Date

3/15/2002

Serial No.

10/098,714

Group

2123

RECEIVED

JUL 23 2002

Technology Center 2100

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,182,718	1/26/1993	Harafuji, et al.	364	490	3/29/1990
	5,432,714	7/11/1995	Chung, et al.	364	525	9/2/1994
	5,533,148	7/2/1996	Sayah, et al.	382	240	9/30/1993
	5,538,815	7/23/1996	Oi, et al.	430	5	9/14/1993
	5,631,110	5/20/1997	Shioiri, et al.	430	5	6/5/1995
	5,657,235	8/12/1997	Liebmann, et al.	364	474.24	5/3/1995
	5,682,323	10/28/1997	Pasch, et al.	364	491	3/6/1995
	5,723,233	3/3/1998	Garza, et al.	430	5	2/27/1996
	5,815,685	9/29/1998	Kamon	395	500	9/15/1995
	5,825,647	10/20/1998	Tsudaka	364	167.03	3/12/1996
	5,885,734	3/23/1999	Pierrat, et al.	430	5	8/15/1996
	5,991,006	11/23/0199	Tsudaka	355	53	10/27/1997
	6,009,250	12/28/1999	Ho, et al.	395	500.06	9/30/1997
	6,009,251	12/28/1999	Ho, et al.	395	500.06	9/30/1997
	6,011,911	1/4/2000	Ho, et al.	395	500.06	9/30/1997
	6,064,806	5/16/2000	Lakos, et al.	395	500.04	10/3/1997
	6,077,310	6/20/2000	Yamamoto, et al.	716	19	1/29/1999
	6,081,658	6/27/2000	Rieger, et al.	395	500.22	12/31/1997
	6,289,499	9/11/2001	Rieger, et al.	716	21	1/7/2000
	6,243,855 B1	6/5/2001	Kobayashi, et al.	716	19	9/29/1998
	6,249,597 B1	6/19/2001	Tsudaka	382	144	12/17/1998
	6,370,679 B1	4/9/2002	Chang, et al.	716	19	9/16/1998
	2002/0010904 A1	1/24/2002	Ayres	716	19	7/23/2001

EXAMINER:

CS ALK

Date Considered:

12/7/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.

NMTC-0770

Serial No.

10/098,714

RECEIVED

Applicant

MACLEAN, Kevin

JUL 23 2002

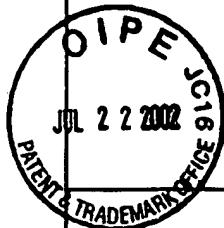
Filing Date

3/15/2002

Group

2123

Technology Center 2100



FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	JP 3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
	WO 00/67074 A1	11/9/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 02/29491 A1	4/11/2002	WO			<input type="checkbox"/>	<input type="checkbox"/>
	GB 2,324,169 A	10/14/1998	GB			<input type="checkbox"/>	<input type="checkbox"/>
	WO 97/38381	10/16/1997	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14636 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14637 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>
	WO 99/14638 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>

date paid filing date

EXAMINER:

Date Considered:

12/7/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

**INFORMATION DISCLOSURE
CITATION**

PTO-1449

Atty. Docket No.

NMTC-0770

Serial No.

10/098,714

Applicant

MACLEAN, Kevin

Filing Date

3/15/2002

Group

2123

RECEIVED

JUL 23 2002

Technology Center 2100

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
SA	Ackmann, P., et al., "Phase Shifting and Optical Proximity Corrections to Improve CD Control on Logic Devices in Manufacturing for Sub 0.35 um I-Line", SPIE, Vol. 3051, pp. 146-153, March 12-14, 1997.
	Lithas, "Lithas: Optical Proximity Correction Software" (2 pages).
	Precim, "Proxima System", Precim Company, Portland, Oregon (2 pages).
	Precim, "Proxima Wafer Proximity Correction System", Precim Company, Portland, Oregon (2 pages).
	Rieger, M., et al., "Mask Fabrication Rules for Proximity-Corrected Patterns", Precim Company, Portland, Oregon (10 pages).
	Rieger, M., et al., "Using Behavior Modeling for Proximity Correction", Precim Company, Portland, Oregon (6 pages).
	Cobb, et al., "Fast Sparse Aerial Image Calculation for OPC", SPIE, Vol. 2621, pp. 534-544, September 20-22, 1995.
	Lucas, K., et al., "Model Based OPC for 1st Generation 193nm Lithography", Motorola Inc., IDT assignee to IMEC (12 pages).
	Stimiman, J., et al., "Quantifying Proximity and Related Effects in Advanced Wafer Processes", Precim Company, Hewlett Packard Labs (9 pages).
	Sugawara, M., et al., "Practical Evaluation of Optical Proximity Effect Correction by EDM Methodology", Sony Corporation (11 pages).
	Saleh, B., et al., "Reduction of Errors of Microphotographic Reproductions by Optimal Corrections of Original Masks", Optical Engineering, Vol. 20, No. 5, pp. 781-784, September/October 1981.
	Fu, C.C., et al., "Enhancement of Lithographic Patterns by Using Serif Features", IEEE, Transactions On Electron Devices, Vol. 38, No. 12, pp. 2599-2603, December 1991.
	Harafuji, K., et al., "A Novel Hierarchical Approach for Proximity Effect Correction in Electron Beam Lithography", IEEE, Vol. 12, No. 10, pp. 1508-1514, October 1993.
	Rieger, M., et al., "System for Lithography Proximity Compensation", Precim Company, Portland, Oregon, September 1993 (28 pages).

EXAMINER:

CSA ALH

Date Considered:

12/7/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE
CITATION

PTO-1449

Atty. Docket No.

NMTC-0770

Serial No.

10/098,714

Applicant

MACLEAN, Kevin

RECEIVED

Filing Date

3/15/2002

Group

2123

JUL 23 2002

Technology Center 2100

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITATION
SA	Galan, G., et al., "Application of Alternating-Type Phase Shift Mask to Polysilicon Level for Random Logic Circuits", Jpn. J. Appl. Phys., Vol. 33, pp. 6779-6784 (1994).
	Stirniman, J., et al., "Fast Proximity Correction with Zone Sampling", SPIE, Vol. 2197, pp. 294-301 (1994).
	Stirniman, J., et al., "Optimizing Proximity Correction for Wafer Fabrication Processes", SPIE, Photomask Technology And Management, Vol. 2322, pp. 239-246 (1994).
	Stirniman, J., et al., "Wafer Proximity Correction and Its Impact on Mask-Making", Bacus News, Vol. 10, Issue 1, pp. 1, 3-7, 10-12, January 1994.
	Henderson, R., et al., "Optical Proximity Effect Correction: An Emerging Technology", Microlithography World, pp. 6-12 (1994).
	Barouch, E., et al., "OPTIMASK: An OPC Algorithm for Chrome and Phase-Shift Mask Design", SPIE, Vol. 2440, pp. 192-206, February 1995.
	Yen, A., et al., "Characterization and Correction of Optical Proximity Effects in Deep-Ultraviolet Lithography Using Behavior Modeling", J. Vac. Sci. Technol. B, Vol. 14, No. 6, pp. 4175-4178, November/December 1996.
	Morimoto, H., et al., "Next Generation Mask Strategy - Technologies are Ready for Mass Production of 256MDRAM?", SPIE, Vol. 3236, pp. 188-189 (1997).
	Park, C., et al., "An Automatic Gate CD Control for a Full Chip Scale SRAM Device", SPIE, Vol. 3236, pp. 350-357 (1997).
	Dolainsky, C., et al., "Application of a Simple Resist Model to Fast Optical Proximity Correction", SPIE, Vol. 3051, pp. 774-780 (1997).
	Tsujimoto, E., et al., "Hierarchical Mask Data Design System (PROPHET) for Aerial Image Simulation, Automatic Phase-Shifter Placement, and Subpeak Overlap Checking", SPIE, Vol. 3096, pp. 163-172 (1997).
	Yamamoto, K., et al., "Hierarchical Processing of Levenson-Type Phase Shifter Generation", Jpn. J. Appl. Phys., Vol. 36, Part 1, No. 12B, pp. 7499-7503, December 1997.
	Chuang, H., et al., "Practical Applications of 2-D Optical Proximity Corrections for Enhanced Performance of 0.25um Random Logic Devices", IEEE, pp. 18.7.1-18.7.4, December 1997.
	Asai, N., et al., "Proposal for the Coma Aberration Dependent Overlay Error Compensation Technology", Jpn. J. Appl. Phys., Vol. 37, pp. 6718-6722 (1998).

EXAMINER:

SA AL

Date Considered:

12/7/05

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.